

**AMENDMENTS TO THE CLAIMS**

Please amend claims 3 and 8 and add new claims 11 through 20 as follows:

1 1. (Original) A tension mask assembly for a flat cathode ray tube, comprising:  
2 a tension mask comprising a plurality of strips separated from one another by a  
3 predetermined gap, real bridges connecting adjacent strips to define slots accommodating electron  
4 beams to pass, and first and second dummy bridges extending from adjacent strips toward each slot  
5 therebetween, said tension mask being installed to include a top surface of said tension mask facing  
6 a panel forming a screen and being separated from said panel by a predetermined gap;  
7 a plurality of supporting members disposed at opposite sides of said tension mask to support  
8 said tension mask; and  
9 a plurality of rigid members secured to opposite ends of said supporting members to apply  
10 tension to said tension mask, a first etching boundary being formed at an end of said first dummy  
11 bridge near to the center of the tension mask being lower with respect to the screen than a second  
12 etching boundary formed at an end of said second dummy bridge near to the periphery of said tension  
13 mask.

1 2. (Original) The tension mask assembly of claim 1, with the vertical center axis of an etched  
2 area at the upper end surfaces of said first and second dummy bridges being offset from the vertical  
3 center axis of an etched area at the lower end surfaces of said first and second dummy bridges toward

the center of said tension mask to accommodate a deflected electron beam being blocked.

3. (Currently Amended) A tension mask assembly for a flat cathode ray tube, comprising:  
a tension mask comprising a plurality of strips separated from one another by a  
predetermined gap, real bridges connecting adjacent strips to define slots accommodating electron  
beams to pass, and first and second dummy bridges extending from adjacent strips toward each slot  
therebetween, said tension mask being installed to include a top surface of said tension mask facing  
a panel forming a screen and being separated from said panel by a predetermined gap;  
a plurality of supporting members disposed at opposite sides of said tension mask to support  
said tension mask; and  
a plurality of rigid members secured to opposite ends of said supporting members to apply  
tension to said tension mask, a first etching boundary being formed at an end of said first dummy  
bridge near to the center of the tension mask being lower with respect to the screen than a second  
etching boundary formed at an end of said second dummy bridge near to the periphery of said tension  
mask,  
with the vertical center axis of an etched area at the upper end surfaces of said first and  
second dummy bridges being offset from the vertical center axis of an etched area at the lower end  
surfaces of said first and second dummy bridges toward the center of said tension mask to  
accommodate a deflected electron beam being blocked,

~~The tension mask assembly of claim 2,~~ with the amount of offset increasing from the center  
of said tension mask toward the periphery of said tension mask.

1           4. (Original) The tension mask assembly of claim 1, with an etched area at the upper end  
2 surfaces of said first and second dummy bridges being wider than an etched area at the lower end  
3 surfaces of said first and second dummy bridges.

1           5. (Original) The tension mask assembly of claim 1, with an etched area at an upper surface  
2 above the first etching boundary of said first dummy bridge being wider than an etched area at a  
3 lower surface therebelow, and an etched area at a lower surface below the second etching boundary  
4 of said second dummy bridge being wider than an etched area at an upper surface thereabove.

1           6. (Original) A tension mask assembly, comprising:  
2 a tension mask including a plurality of strips separated from one another by a predetermined  
3 gap, real bridges connecting adjacent strips to define slots accommodating electron beams to pass,  
4 and first and second dummy bridges extending from adjacent strips toward each slot therebetween,  
5 said tension mask being installed to include a top surface of said tension mask facing a panel forming  
6 a screen and being separated from said panel by a predetermined gap, a first etching boundary being  
7 formed at an end of said first dummy bridge near to the center of the tension mask being lower with  
8 respect to the screen than a second etching boundary formed at an end of said second dummy bridge  
9 near to the periphery of said tension mask.

1           7. (Original) The tension mask assembly of claim 6, with the vertical center axis of an etched

2 area at the upper end surfaces of said first and second dummy bridges being offset from the vertical  
3 center axis of an etched area at the lower end surfaces of said first and second dummy bridges toward  
4 the center of said tension mask to accommodate a deflected electron beam being blocked.

1 8. (Currently Amended) A tension mask assembly, comprising:

2 a tension mask including a plurality of strips separated from one another by a predetermined  
3 gap, real bridges connecting adjacent strips to define slots accommodating electron beams to pass,  
4 and first and second dummy bridges extending from adjacent strips toward each slot therebetween,  
5 said tension mask being installed to include a top surface of said tension mask facing a panel forming  
6 a screen and being separated from said panel by a predetermined gap, a first etching boundary being  
7 formed at an end of said first dummy bridge near to the center of the tension mask being lower with  
8 respect to the screen than a second etching boundary formed at an end of said second dummy bridge  
9 near to the periphery of said tension mask,

10 with the vertical center axis of an etched area at the upper end surfaces of said first and  
11 second dummy bridges being offset from the vertical center axis of an etched area at the lower end  
12 surfaces of said first and second dummy bridges toward the center of said tension mask to  
13 accommodate a deflected electron beam being blocked,

14 ~~The tension mask assembly of claim 7,~~ with the amount of offset increasing from the center  
15 of said tension mask toward the periphery of said tension mask.

1 9. (Original) The tension mask assembly of claim 6, with an etched area at the upper end

2 surfaces of said first and second dummy bridges being wider than an etched area at the lower end  
3 surfaces of said first and second dummy bridges.

A2  
end  
1 10. (Original) The tension mask assembly of claim 6, with an etched area at an upper surface  
2 above the first etching boundary of said first dummy bridge being wider than an etched area at a  
3 lower surface therebelow, and an etched area at a lower surface below the second etching boundary  
4 of said second dummy bridge being wider than an etched area at an upper surface thereabove.

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1 11. (New) A tension mask assembly, comprising:  
2 a tension mask, comprising:  
3 a plurality of strips separated from one another by a predetermined gap;  
4 real bridges connecting adjacent strips to define slots accommodating electron beams  
A3  
Cont'd  
to pass; and  
6 first and second dummy bridges extending from adjacent first and second strips,  
7 respectively, toward each slot therebetween, said tension mask being installed to include a top  
8 surface of said tension mask facing a panel forming a screen and being separated from said panel by  
9 a predetermined gap,  
10 with each one of the slots on a first portion of the tension mask including a first  
11 etching boundary being formed at an end of the first dummy bridge near to the center of the tension  
12 mask being lower with respect to the screen than a second etching boundary formed at an end of the  
13 second dummy bridge near to the periphery of said tension mask, and at a section of the slots without

14 the dummy bridges including a third etching boundary being formed at an end of the first strip near  
15 to the center of the tension mask being higher with respect to the screen than a fourth etching  
16 boundary formed at an end of the second strip near to the periphery of the tension mask; and  
17 a first unit supporting and applying tension to said tension mask.

1 12. (New) The tension mask assembly of claim 11, further comprising a center portion of the  
2 tension mask including slots with first and second dummy bridges being symmetric with each other  
3 where an etched area at an upper end surface of the first and second dummy bridges is substantially  
4 the same as an etched area at lower end surfaces of the first and second dummy bridges.

1 13. (New) The tension mask assembly of claim 12, further comprising a peripheral portion  
2 of the tension mask including slots with a first etching boundary being formed at an end of a first  
3 dummy bridge near to the center of the tension mask being lower with respect to the screen than a  
4 second etching boundary formed at an end of a second dummy bridge near to the periphery of said  
5 tension mask, the first dummy bridge of the peripheral portion being nearer to the center of the  
6 tension mask than the second dummy bridge and the second dummy bridge being nearer to the  
7 periphery of the tension mask than the first dummy bridge of the peripheral portion.

1 14. (New) The tension mask assembly of claim 13, with an etched area at the upper end  
2 surfaces of said first and second dummy bridges being wider than an etched area at the lower end  
3 surfaces of said first and second dummy bridges.

1 15. (New) The tension mask assembly of claim 14, with an etched area at an upper surface  
2 above the first etching boundary of said first dummy bridge being wider than an etched area at a  
3 lower surface therebelow, and an etched area at a lower surface below the second etching boundary  
4 of said second dummy bridge being wider than an etched area at an upper surface thereabove.

1 16. (New) The tension mask assembly of claim 15, with the etched area at the top surfaces  
2 of the first and second strips being wider than the etched area at the lower surface of the first and  
3 second strips where the top surfaces of the first and second strips face the screen.  
4

1 17. (New) The tension mask assembly of claim 16, with the vertical center axis of an etched  
2 area at the upper end surfaces of said first and second dummy bridges being offset from the vertical  
3 center axis of an etched area at the lower end surfaces of said first and second dummy bridges toward  
4 the center of said tension mask to accommodate a deflected electron beam being blocked,  
5 with the amount of offset increasing from the center of said tension mask toward the  
6 periphery of said tension mask.

1 18. (New) The tension mask assembly of claim 11, with the vertical center axis of an etched  
2 area at the upper end surfaces of said first and second dummy bridges being offset from the vertical  
3 center axis of an etched area at the lower end surfaces of said first and second dummy bridges toward  
4 the center of said tension mask to accommodate a deflected electron beam being blocked.

1 19. (New) The tension mask assembly of claim 18, with the amount of offset increasing from  
2 the center of said tension mask toward the periphery of said tension mask.

1 20. (New) A tension mask assembly, comprising:

2 a tension mask, comprising:

3 a plurality of strips separated from one another by a predetermined gap;

4 real bridges connecting adjacent strips to define slots accommodating electron beams  
5 to pass; and

6 first and second dummy bridges extending from adjacent first and second strips,  
7 respectively, toward each slot therebetween, said tension mask being installed to include a top  
8 surface of said tension mask facing a panel forming a screen and being separated from said panel by  
9 a predetermined gap, an etched depth at each one of the upper end surfaces of the first and second  
10 dummy bridges being substantially the same as an etched depth at each one of the lower end surfaces  
11 of the first and second dummy bridges where the first dummy bridge is near to the center of the  
12 tension mask and the second dummy bridge is near to the periphery of said tension mask, and a  
13 portion without the dummy bridges of each of the slots including a third etching boundary being  
14 formed at an end of the first strip near to the center of the tension mask being higher with respect to  
15 the screen than a fourth etching boundary formed at an end of the second strip near to the periphery  
16 of said tension mask; and

17 a first unit supporting and applying tension to said tension mask.